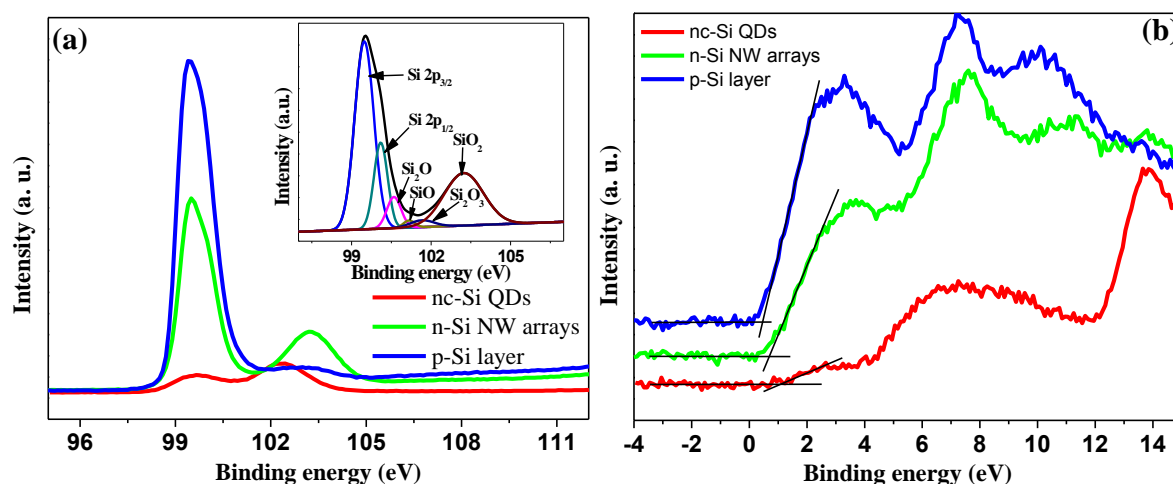


# High Efficiency Hybrid Solar Cells Using Nanocrystalline Si Quantum Dots and Si Nanowires

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## Supporting information

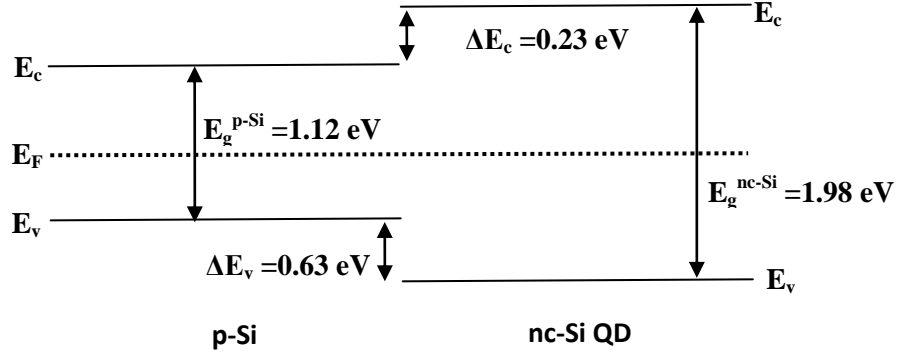


**Figure S1.** (a) High resolution Si 2p and (b) valence band XPS spectrum of nc-Si QDs, n-Si NW arrays and p-Si layer.

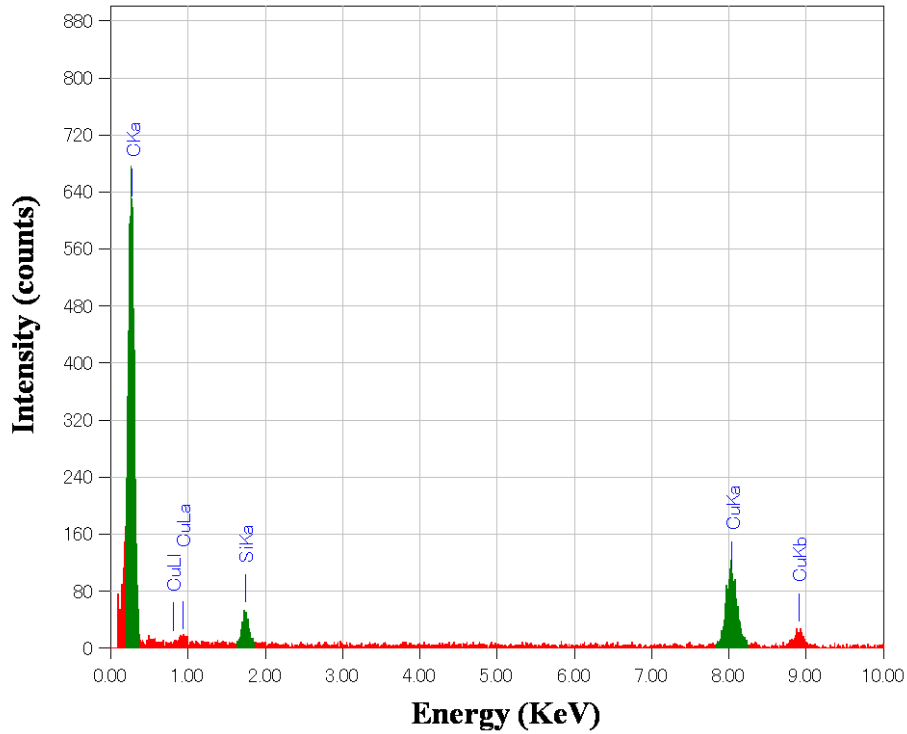
Figure S1a shows the Si 2p XPS spectrum of the components of the hybrid solar cell. All the spectra show the presence of two peaks: one assigned to the metallic Si  $2p^{3/2}$  of silicon and another  $Si^{4+} 2p^{3/2}$  of sub oxides on the surface [1]. Deconvolution of the Si 2p spectrum reveals the presence of  $Si_2O$ ,  $SiO$ ,  $Si_2O_3$  or rather more specifically intermediate oxidation states  $Si^{1+}$ ,  $Si^{2+}$ ,  $Si^{3+}$  (inset to Figure S1a is a representative deconvoluted spectrum) [2-5]. The presence of an oxide layer on the surface of nc-Si QDs demonstrates the growth of oxide layer on HF-etched Si nanocrystals during capping. Presence of this oxide layer may be a possible cause of the low quantum yield (30%) of these nc-Si QDs. The XPS spectrum of the valence band (VB) shows a sharp rise near 0.69 eV, 0.47 eV and 1.1 eV, associated with the onset of the VB of n-Si nanowire arrays, polycrystalline p-Si film and nc-Si QDs, respectively. The VB maximum positions are determined by a linear extrapolation of the leading edge of the photoelectron valence-band spectrum back to the energy axis. Defining the slope intercept as the VBM is widely used to determine the VBM of semiconductors to an accuracy of about 0.1 eV [6, 7]. From the above measurements, the valence band offset ( $\Delta E_v$ ) value in the interface between the p-Si layer and nc-Si QDs can be estimated to be  $\sim 0.63$  eV. Using this  $\Delta E_v$  conduction band offset can be estimated using

$$\Delta E_c = \Delta E_v + E_g^{\text{p-Si}} - E_g^{\text{nc-Si}}$$

where  $E_g^{\text{nc-Si}}$  and  $E_g^{\text{p-Si}}$  are the band gap of nc-Si QDs and p-Si layer respectively. Assuming the bandgap of p-Si layer to be close to that of bulk Si,  $\Delta E_c$  can be estimated as ~0.23 eV. Thus, this measurement indicates type I band alignment in the interface of the p-Si layer and nc-Si QDs, as shown in Figure S2 (ignoring the presence of SiO<sub>2</sub> for simplicity).



**Figure S2.** Band alignment at the interface of p-Si layer and nc-Si QDs



**Figure 3.** EDS spectrum of nc-Si QDs

The composition of the nc-Si QDs was confirmed by energy dispersive X-ray (EDX) spectroscopy (Figure S3), demonstrating that samples consist of Si. However no traces of O

element was detected in comparison with XPS measurement [Figure S1 (a)] because XPS is a surface sensitive technique and XPS measurements suggest very low amount of oxides that may be lower than the detection level of EDX measurement. The C peak arises from the surface bonded alkyl groups and the holey carbon films on a TEM grid. They cannot be differentiated. Cu peaks are due to the TEM grid of Cu.

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